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7/15/03

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q55902

Makoto KASHIWAYA et al.

Appln. No.: 09/534,207

Group Art Unit: 1765

Confirmation No.: 2981

Examiner: Duy Vu Nguyen DEO

Filed: March 24, 2000

For: CARBON LAYER FORMING METHOD

AMENDMENT UNDER 37 C.F.R. § 1.111

MAIL STOP NON-FEE AMENDMENT

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

RECEIVED
JUL 01 2003
TC 1700

Sir:

In response to the Office Action dated March 3, 2003, please amend the application as follows:

IN THE CLAIMS:

Please enter the following new claims:

9. (New) The method according to claim 1, wherein said step of adjusting the content of particles includes cleaning an interior of a chamber of the film deposition system in which the film deposition process occurs using a dust cloth that produces no more than 3000 particles/cfm.